



Highlights

- Highly economical
- Reduces scratching due to plate/pad contamination
- Minimizes scratching from in-process handling
- Prevents staining
- Facilitates downstream cleaning processes
- Minimizes plate/pad cleaning and maintenance

Detergent

VECTOR HTR

VECTOR HTR is a synthetic formulation developed for the rinsing and wet storage of substrates after lapping, polishing, sawing or texturing. Used as directed, VECTOR HTR minimizes scratching from in-process handling; protects substrates from staining; and prevents hard-to-clean slurry residues from adhering to the substrate surface for more effective downstream cleaning.

VECTOR HTR is recommended for use on mono-crystalline and multi-crystalline silicon. For solar silicon producers, VECTOR HTR is used to rinse excess slurry residues from wafers post-wire sawing. Before demounting, the wafers are rinsed with a solution of 3% to 4% VECTOR HTR and DI water to eliminate staining and improve final cleaning results. VECTOR HTR is also used to wet-store wafers after demounting and prior to cleaning.

For semiconductor silicon producers, VECTOR HTR is recommended for the rinsing and washing of lapping plates. VECTOR HTR removes process debris from both the plate's surface and grooves, thereby preventing the formation of iron oxide/abrasive particle aggregates that can dislodge and cause scratching. When used for rinsing and washing polishing pads, VECTOR HTR prevents staining; increases pad life by keeping the pore structure open; and reduces the frequency of pad conditioning.

Typical applications

Gallium arsenide, germanium, sapphire, silicon, silicon carbide

Slurry additive	Base material	Dilution ratio	pH value	Specific gravity
VECTOR HTC-SCA-1	Water	25:1	9.2	1.05
VECTOR HTR	Water	30:1	9.8	1.03



VECTOR HTR is useful for keeping glass or silicon off cast-iron plates.



VECTOR HTR is a more effective solution for wafer storage post-lap or post-polish, neutralizing ions on the wafer surface to prevent attachment.



Pureon offers a wide range of customized solutions. More information can be found on www.pureon.com/products/overview

Product specifications

Base material Water
Shelf life 24 months

Order information

Packing Product is available in 5-gallon pails and 55-gallon drums. Other sizes available upon request.
Unit of measure Gallon [gal]

Application recommendations

Handling Post wire-saw solar silicon wafers should be immersed while still mounted into a bath of 3 % to 4 % VECTOR HTR in DI water, to prevent slurry residues from adhering to wafers and improve the results of subsequent cleaning and etching processes.

Post-lapping or polishing, VECTOR HTR is used at dilutions ranging from 2 % to 3 %, depending on the condition and type of lapping equipment and the wafers.

After the lapping plate has lifted, VECTOR HTR should be flooded over the surface. This breaks the surface tension between the wafers and the plate, and removes any remaining contamination, which could cause scratching and complicate handling. Wafers can then be removed, re-rinsed and stored in a 2 % HTR bath. For polishing applications follow the same dilution guidelines.

Storage Product should be stored in a temperature controlled environment. Prolonged exposure to temperatures at or below 32 ° Fahrenheit (0 °C) is discouraged. Prolonged exposure to temperatures at or above 100 ° Fahrenheit (38 °C) is also discouraged. In addition, material should always be sealed when not in use to prevent evaporation.

Disposal Dispose of in accordance with all applicable local regulations.

This product is manufactured by Intersurface Dynamics.

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